Photomask Blank and Method for Preparing Photomask

ABSTRACT

A photomask blank comprising a transparent substrate and a light-shielding film disposed thereon is provided. The light-shielding film is constructed by a single layer or multiple layers including a light-shielding layer containing Si and N, having a N content of 3-50 at% based on the sum of Si and N, being free of a transition metal.

(no suitable figure)